

Sub E1
cont'd
B3
11. (Amended) A coated substrate having a thin film optical coating in accordance with claim 1, wherein the substrate has a melting point temperature [greater than or equal to about 100 °C] less than or equal to about 450 °C.

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12. (Amended) A thin film optical coating for use on a substrate, having a layer comprising a sol-gel derived oxide system, the sol-gel derived oxide system comprising niobium oxide, silicon dioxide and aluminum oxide, wherein the layer is capable of providing an index of refraction of from about 1.60 to about 1.90.

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13. (Amended) A coated substrate having a thin film optical coating in accordance with claim ^A12, wherein the substrate has a melting point temperature [greater than or equal to about 100 °C] less than or equal to about 450 °C.

Sub E1
cont'd
B3
14. (Amended) An optical filter comprising a thin film optical coating produced by [the process of claim 14]:

(a) immersing the substrate in a mixture comprising niobium chloride, a silicon precursor, an aluminum precursor, and an alcohol, wherein the molar ratio of niobium to silicon is from about 0.9:1 to about 3.6:1 and the molar ratio of niobium to aluminum is from about 0.8:1 to about 3.0:1;

(b) withdrawing the substrate from the mixture to provide the substrate with a coating of the mixture; and

(c) heat-treating the substrate to form a layer having an index of refraction of from about 1.60 to about 1.90.

Please add new claim 21:

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21 (New) The coating according to claim 12, wherein the niobium oxide is present in the layer in a mole fraction of from about 0.22 to about 0.53, the silicon oxide is present in the